

U. S. PATENT DOCUMENTS

Examiner Initial	Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
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<u>AP E</u>	6,006,694	12/28/99	DeOrnellas et al.	118	723 I	
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JUL 20 2001

PATENT & TRADEMARK OFFICE

FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Publication Date	Name	Class	Subclass	Translation If Appropriate
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<u>AP</u>	EP 0421348	04/10/91	Tamura et al.	C23C	14/35	
	EP 0650182	04/26/95	Rice et al.	H01J	37/32	
	EP 0727807	08/21/96	Hanawa et al.	H01J	37/32	
	EP 0732729	09/18/96	Kanai et al.*	H01J	37/32	
	EP 0838841	04/29/98	Schneider et al.	H01J	37/32	
<u>AP</u>	JP 07221070	08/18/95	Kadomuro Shingo	H01L	21/3065	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

AP Lee et al., "Patterning of Pt thin films using SiO₂ mask in a high density plasma", *J. Kor. Inst. Telematics & Elect.*, Vol.34D, No.3, pp.187 - 192 (1997).

AP Lieberman et al., "Plasma Sources for Thin Film Deposition and Etching", *Physics of Thin Films: Advances in Research and Development*, Vol. 18, Maurice H. Francombe and John L. Vossen, eds., Academic Press, Inc., San Diego, pp. 10-13, 30, 31, 52, 53, 60, 61 (1994).

Alta c Ola 5/27/2003

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* Cited by the Examiner in the parent application.

FORM PTO-1449
(Equivalent)

U.S. Department of Commerce
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U.S. Application Serial No.

Atty. Docket No.

~~Not yet assigned~~

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09/896,785

INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

Jeng H. Hwang et al.
Applicants

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Filing Date

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Group

(Use several sheets if necessary)



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<u>AWO</u>	5,110,408	05/05/92	Fujii et al.	156	643	
	5,419,029	05/30/95	Raaijmakers	29	447	
	5,569,363	10/29/96	Bayer et al.	204	192.32	
	5,599,403	02/04/97	Kariya et al.	136	258	
	5,614,055	03/25/97	Fairbairn et al.	156	345	
	5,641,375	06/24/97	Nitescu et al.	156	345	
	5,685,941	11/11/97	Forster er al.	156	345	
	5,686,339	11/11/97	Lee et al.*	437	52	
	5,753,044	05/19/98	Hanawa et al.	118	723 I	
	5,763,851	06/09/98	Forster et al.*	219	121.43	
	5,800,688	09/01/98	Lantsman et al.	204	298.11	
<u>AWO</u>	5,837,057	11/17/98	Koyama et al.	118	723 VE	

Allen C. Chan 5/27/2003
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